Page 1 of 3 Form PTO-1449 U.S. DEPARTMENT OF COMMERCE ATTY, DOCKET NO. SERIAL NO. (MODIFIED) PATENT AND TRADEMARK OFFICE 039153-0256 (F0113) 09/599,141 **APPLICANT** INFORMATION DISCLOSURE CITATION Yu FILING DATE **GROUP ART UNIT** SEP 0 4 2003 (Use several sheets if necessary) 06/22/2000 2812 **U.S. PATENT DOCUMENTS** FILING DATE EXAMINER DOCUMENT SUB-REF DATE NAME **CLASS** INITIAL NUMBER CLASS APPROPRIATE **A1** 6,461,945 10/8/2002 Yu 6,350,311 A2 2/26/2002 Chin et al. 6,319,799 **A3** 11/20/2001 Ouyang et al. A4 6,310,367 10/30/2001 Yagishita et al. **A5** 6,268,640 7/31/2001 Park, et al. **A6** 6,232,622 5/15/2001 Hamada 6,190,975 2/20/2001 Kubo et al. **A7** 1/9/2001 Gardner et al. **A8** 6,172,381 6,133,082 10/17/2000 Masuoka Α9 6,130,144 10/10/2000 Verret A10 6,031,269 A11 2/29/2000 Liu A12 6,022,785 2/8/2000 Yeh, et al. 11/16/1999 A13 5,985,703 Banerjee A14 5,981,345 11/9/1999 Ryum, et al. 5,936,280 8/10/1999 A15 5,910,015 6/8/1999 Sameshima, et al. A16 5,856,225 01/5/1999 Lee et al. A17 5,821,149 10/13/1998 Schuppen et al. A18 5,766,989 6/16/1998 Maegawa et al. A19 5.753.541 5/19/1998 Shimizu A20 5,689,136 11/18/1997 Usami et al. A21 5,683,934 11/4/1997 Candelaria A22 A23 5,675,185 10/7/1997 Chen et al. A24 5,612,552 3/18/1997 Owens A25 5,591,653 1/7/1997 Sameshima, et al. 5,581,101 A26 12/3/1996 Ning et al. 5,554,870 9/10/1996 A27 Fitch et al. M **EXAMINER DATE CONSIDERED** 12/23/03

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